

# Abstracts

## Comparison of power dependence of microwave surface resistance of unpatterned and patterned YBCO thin film

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The effect of the patterning process on the nonlinearity of the microwave surface resistance  $R_{\text{sub s}}$  of YBCO thin films is investigated in this paper. With the use of a sapphire dielectric resonator and a stripline resonator, the microwave  $R_{\text{sub s}}$  of YBCO thin films was measured before and after the patterning process, as a function of temperature and the RF peak magnetic field in the film. The microwave loss was also modeled, assuming a  $J_{\text{sub rf}}^{\text{sup 2}}$  dependence of  $Z_{\text{sub s}}(J_{\text{sub rf}})$  on current density  $J_{\text{sub rf}}$ . Experimental and modeled results show that the patterning has no observable effect on the microwave residual  $R_{\text{sub s}}$  or on the power dependence of  $R_{\text{sub s}}$ .

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